



Aktuelles Experiment:

noname.rcp

Modellbeschreibung

Number	Layer Name	Thickness [nm]	Refr. Index	Fitted
			[632.8 nm]	
0	Air	-	1.000	no
1	NoName0	170.73	2.710	yes
2	Silicon DUV-NIR -		3.874	no

Fit parameter

Fit parameter	F	it result
[1,1] NoName0: Thickness [[nm] 1	70.73

All parameter

Value
632.8
70.00
0.0
23.5
0.00
1.0000
0.0000
0.0000
4.00
4.00
10.0
0.0
3.0
0.00
0.00
1.00000
1.000
1.000
1.000
0.000
0.00000
0.00000



[1,1] NoName0: Thickness [nm]	170.73
NoName0: N0	2.700
NoName0: N1	40.0
NoName0: N2	0.0
NoName0: K0	0.000
NoName0: K1	0.000
NoName0: K2	0.000
NoName0: N Offset	0.00000
NoName0: K Offset	0.00000
Silicon DUV-NIR: N Offset	0.00000
Silicon DUV-NIR: K Offset	0.00000
Pola.Pos.	45.00
Pola.Offs.	0.00
Ret.Axis	0.00
Ret.Phase	90.00
Eta	1.00000
Ana.Offs.	0.00
Ana.Offs.Lin.	0.00
Ana.Offs.Quadr.	0.00
Psi Offs.	0.00
Psi Lin.	0.00
Psi Quadr.	0.00
Delta Offs.	0.00
Delta Lin.	0.00
Delta Quadr.	0.00
MSE	63 6129791

63.61287816 MSE

Measured Data

RRM001-045 / Psi, Delta / Spectral range: 300.2 nm - 1050.0 nm / Angle of incidence: 60.00 $^{\circ}$ / 9/17/2019 2:54:54 PM



